ABSTRACT OF THE DISCLOSURE

In a transparent laminate, n thin-film units (n=3 or 4) are laminated unit by unit successively on a surface of a substrate, and a high-refractive-index transparent thin film is deposited on a surface of the laminate of the n thin-film units, each of the n thin-film units consisting of a high-refractive-index thin film and a silver transparent conductive thin film. When the silver transparent conductive thin films are deposited by a vacuum dry process, the temperature T(K) of the transparent substrate at the time of film deposition is set to be in a range $340 \leqq T \leqq 410$, whereby the transparent laminate having a standard deviation of visible light transmittance which is not larger than 5 % in a wave range of from 450 to 650 nm can be produced.